

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants:	Gabric, et al.	Docket No.:	INF 2006 VJ 33543 US
Serial No.:	10/586,788	Art Unit:	2893
Filed:	September 2, 2008	Examiner:	Nikolay K. Yushin
Title:	Plasma Excited Chemical Vapor Deposition Method, Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly		

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT**

Dear Sir:

The Applicants wish to bring to the attention of the U.S. Patent and Trademark Office the information noted on the enclosed form PTO/SB/08a, which may be considered material to the examination of the above-identified application. Copies of the U.S. Patents and Publications cited are not being submitted.

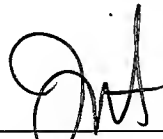
This Information Disclosure Statement is submitted under 37 C.F.R. §1.97(c) together with a \$180.00 fee under 37 C.F.R. §1.17(p) after the C.F.R. §1.97(b) time period, but before final action or notice of allowance, whichever occurs first.

Please charge the required fee of \$180.00 and any additional amount, or credit any overpayment to Deposit Acct. No. 50-1065 of the below mentioned firm.

Respectfully submitted,

9/4/09

Date



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